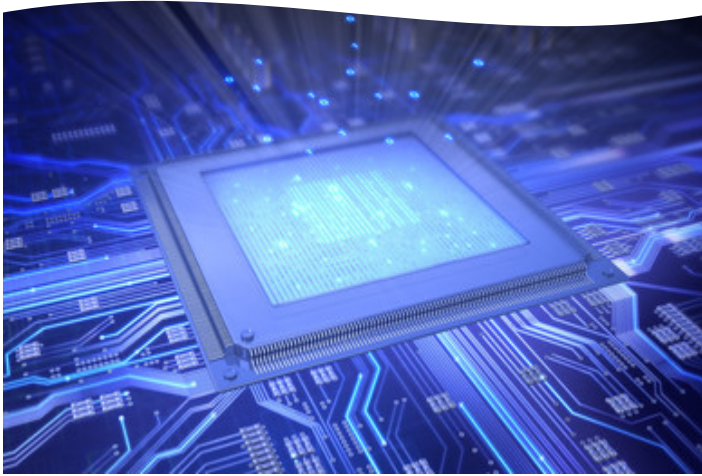


¹¹B in the Form of Boron Trifluoride Gas for Semiconductor Manufacture



Boron trifluoride gas is the ideal silicon wafer dopant for the production of highly integrated, high-density microchips. $^{11}\text{BF}_3$ provides for greater efficiency and increased production throughput, and helps to make chips smaller and better.

¹¹B in the Form of ¹¹BF₃ Gas

Specification

Physical properties:

- Material ¹¹B – Boron-11 in the form of Boron Trifluoride Electronic Grade
- Enrichment ¹¹B > 99,8at%

Chemical Properties:

- Form BF₃
- Purity > 99,9vol%

Impurities in vppm

| | |
|------------------|-------|
| Ar | ≤ 25 |
| O ₂ | ≤ 25 |
| CO ₂ | ≤ 25 |
| HF | ≤ 25 |
| N ₂ | ≤ 25 |
| SiF ₄ | ≤ 100 |
| SO ₂ | ≤ 25 |

Our gas is fully compatible with VLIS-requirements.

NUKEM Isotopes GmbH

Industriestrasse 13, 63755 Alzenau, Germany, T: +49 (0)6023 911611, F: +49 (0)6023 911614
E: info@nukemisotopes.de, I: www.nukem-isotopes.com